

**METHOD OF LITHOGRAPHIC IMAGE ALIGNMENT FOR USE WITH A DUAL
MASK EXPOSURE TECHNIQUE**

ABSTRACT OF THE DISCLOSURE

5 Methods of fabricating an integrated circuit on a wafer using dual mask
exposure lithography is disclosed. Improved mask image alignment between a
first mask image and a second mask image of a dual mask exposure technique
can be achieved by aligning the second mask image to a latent image created by
an exposure using the first mask image.

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